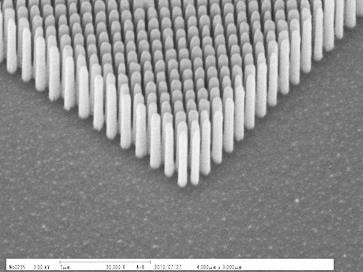
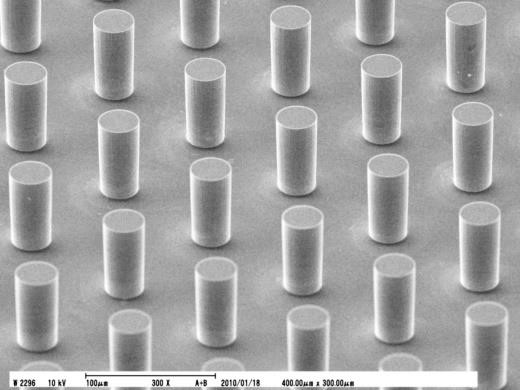
**ICP (Elionix EIS 700)** 簡介

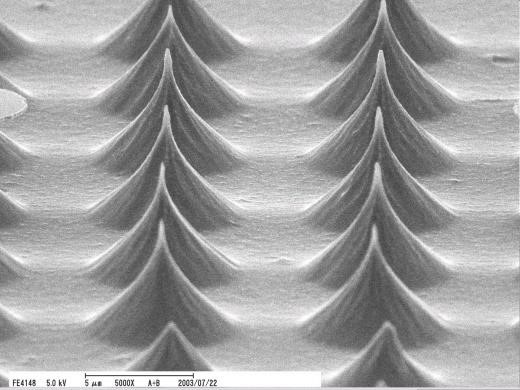
1. 儀器全名：電感耦合電漿蝕刻系統 (Inductively Coupled Plasma Etching System 型號：EIS-700)



Elionix



Elionix



Elionix

1. 服務簡介：

EIS-700 具可程式化與配有1 KW高頻輸出電壓進行蝕刻製程。本機台配有Ar, O2, C4F8, SF6四種氣體，所有蝕刻參數步驟可經由電腦自動化控制；EIS-700可達到良好的蝕刻準直性，以更短時間取得較高或較深的結構。

1. 儀器規格：

|  |  |
| --- | --- |
| Sample size | Max to 6 inch wafer |
| High frequency power supply | 1 KW (Max) |
| Bias power supply | 300 W (Max) |
| Gas flow | Ar, O2, C4F8, SF6 |

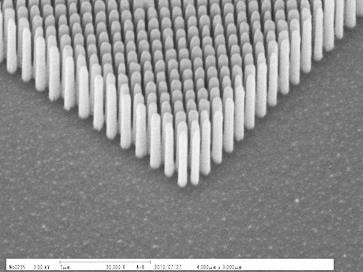
1. 收費標準：

尖峰時間(9am-19pm)：1,500 NTD/2hr 離峰時間(19pm-9am)：1,000 NTD/2hr

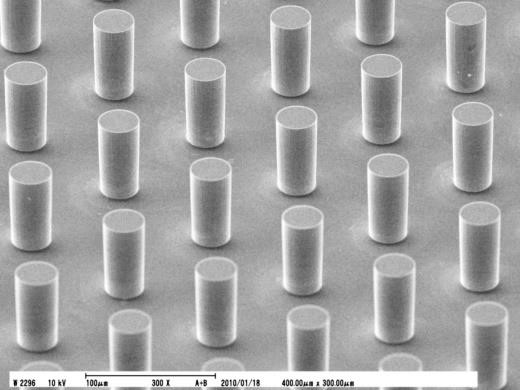
1

**ICP (Elionix EIS 700)**

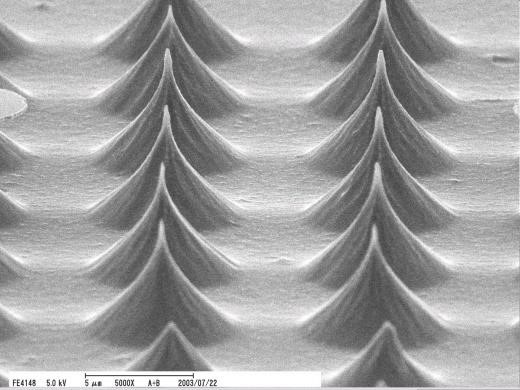
1. MODEL：Elionix EIS-700 Inductively Coupled Plasma Etching System



Elionix



Elionix



Elionix

1. Introduction：

EIS-700 is equipped with programming function for etching and 1 KW high frequency output for good producibility. All etching process can be operated automatically by CPU control, supplying Ar, O2, C4F8, SF6 gas flow for fluorine etching process.EIS-700 can achieve excellent anisotropic etching characteristic compatible with high aspect cross-sectional shape for high speed application.

1. Spec：

|  |  |
| --- | --- |
| Sample size | Max to 6 inch wafer |
| High frequency power supply | 1 KW (Max) |
| Bias power supply | 300 W (Max) |
| Gas flow | Ar, O2, C4F8, SF6 |

1. Chargement：

Rush Hour(9am-19pm)：1,500 NTD/2hr

Off-peak(19pm-9am)：1,000 NTD/2hr

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